

Title (en)

FLUOROPOLYMER INTERLAYER DIELECTRIC BY CHEMICAL VAPOR DEPOSITION

Title (de)

FLUORPOLYMER-ZWISCHENSCHICHTDIELEKTRIKUM DURCH CHEMISCHE GASPHASENABSCHEIDUNG

Title (fr)

DIELECTRIQUE INTERCOUCHES EN FLUOROPOLYMERES FORME AU MOYEN D'UN PROCEDE DE DEPOT CHIMIQUE EN PHASE VAPEUR

Publication

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Application

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Priority

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Abstract (en)

[origin: WO2004001832A1] A process is disclosed for forming a fluoropolymer layer on a thin film device, comprising contacting said thin film device with a gas phase fluoromonomer, and initiating polymerization of said fluoromonomer with a free radical polymerization initiator whereby said fluoromonomer polymerizes to form said fluoropolymer layer on said thin film device.

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IPC 8 full level

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CPC (source: EP)

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